

### AMENDMENTS TO THE CLAIMS

1. (Original) A processing liquid coating apparatus for coating a surface of a substrate with a processing liquid, said apparatus comprising:  
a substrate holder for holding and rotating the substrate; and  
a processing liquid supply unit disposed apart from the substrate held by said substrate holder;  
wherein said processing liquid supply unit has a plurality of supply ports for supplying the processing liquid to a plurality of portions including a central portion of the surface of the substrate, and the processing liquid is a resist liquid or a developer.
2. (Original) A processing liquid coating apparatus according to claim 1, wherein said processing liquid supply unit has a plurality of suction ports for sucking the processing liquid on the substrate.
3. (Original) A processing liquid coating apparatus according to claim 2, wherein said plurality of supply ports and said plurality of suction ports are arranged alternately and linearly.
4. (Original) A processing liquid coating apparatus according to claim 1, wherein said processing liquid supply unit is movable in a radial direction of the substrate.
5. (Currently Amended) A processing liquid coating apparatus according to ~~any one of claims 1 to 4~~ claim 1, further comprising a processing liquid suction unit for sucking the processing liquid from a peripheral portion of the substrate.
6. (Currently Amended) A processing liquid coating apparatus according to ~~any one of claims 1 to 5~~ claim 2, further comprising a gas supply unit for ejecting a gas toward the surface of the substrate, said gas supply unit being movable from the central portion to a peripheral portion of the substrate.

7. (Original) A processing liquid coating method for coating a surface of a substrate with a processing liquid, said method comprising:

rotating the substrate; and

supplying the processing liquid to a plurality of portions including a central portion of the surface of the substrate;

wherein the processing liquid is a resist liquid or a developer.

8. (Original) A processing liquid coating method according to claim 7, further comprising sucking the processing liquid from a plurality of portions of the surface of the substrate.

9. (Original) A processing liquid coating method according to claim 7, further comprising sucking the processing liquid from a plurality of portions including a peripheral portion of the surface of the substrate.

10. (Currently Amended) A processing liquid coating method according to ~~any one of claims 7 to 9~~ claim 7, further comprising:

ejecting a gas from a gas supply unit toward the surface of the substrate; and

moving said gas supply unit from the central portion to a peripheral portion of the substrate.

11. (New) A processing liquid coating apparatus according to claim 2, further comprising a processing liquid suction unit for sucking the processing liquid from a peripheral portion of the substrate.

12. (New) A processing liquid coating apparatus according to claim 3, further comprising a processing liquid suction unit for sucking the processing liquid from a peripheral portion of the substrate.

13. (New) A processing liquid coating apparatus according to claim 4, further comprising a processing liquid suction unit for sucking the processing liquid from a peripheral portion of the substrate.

14. (New) A processing liquid coating apparatus according to claim 2, further comprising a gas supply unit for ejecting a gas toward the surface of the substrate, said gas supply unit being movable from the central portion to a peripheral portion of the substrate.

15. (New) A processing liquid coating apparatus according to claim 3, further comprising a gas supply unit for ejecting a gas toward the surface of the substrate, said gas supply unit being movable from the central portion to a peripheral portion of the substrate.

16. (New) A processing liquid coating apparatus according to claim 4, further comprising a gas supply unit for ejecting a gas toward the surface of the substrate, said gas supply unit being movable from the central portion to a peripheral portion of the substrate.

17. (New) A processing liquid coating apparatus according to claim 5, further comprising a gas supply unit for ejecting a gas toward the surface of the substrate, said gas supply unit being movable from the central portion to a peripheral portion of the substrate.

18. (New) A processing liquid coating method according to claim 8, further comprising:

ejecting a gas from a gas supply unit toward the surface of the substrate; and

moving said gas supply unit from the central portion to a peripheral portion of the substrate.

19. (New) A processing liquid coating method according to claim 9, further comprising:  
ejecting a gas from a gas supply unit toward the surface of the substrate; and  
moving said gas supply unit from the central portion to a peripheral portion of the substrate.